## Notice of References Cited Application/Control No. | Applicant(s)/Patent Under Reexamination | MALDEI ET AL. | Examiner | Art Unit | Page 1 of 1

## **U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-4,956,313	09-1990	Cote et al.	438/672
	В	US-5,814,862	09-1998	Sung et al.	257/344
	С	US-6,236,079	05-2001	Nitayama et al.	257/306
	D	US-6,383,868	05-2002	Parekh et al.	438/253
	Ε	US-6,690,050	02-2004	Taniguchi et al.	257/306
	F	US-6,521,938	02-2003	Hamamoto, Takeshi	257/304
	G	US-			
	Н	US-			
	_	US-			
	J	US-			
	К	US-			
	L	US-			
	М	US-			

## FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0					
	Р					
	Q					
	R					
	S			1,500		
	Т					

## **NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
x	U	Wolf et al., Silicon Processing for The VLSI Era, Volume 1: Process Technology, Pp. 184, (1986).
	v	
	w	
	х	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.